

ABSTRACT

WASHING DEVICE AND WASHING METHOD

A washing device includes: a plurality of spindles 51 which holds a substrate W and rotates the substrate W about a central axis of the substrate W as a rotary axis; and a single tube nozzle 41 which discharges a washing liquid L toward an upper surface of the substrate W, wherein the single tube nozzle 41 discharges the washing liquid L so that the washing liquid L lands in front of the center O of the substrate W and the landed washing liquid L flows on the upper surface of the substrate W toward the center of the substrate W. A liquid flow on the upper surface of the substrate W after landing of the washing liquid L discharged from the single tube nozzle 41 passes through the center O of the substrate W.

Figure 2